

Korean International Semiconductor Conference & Exhibition on Manufacturing Technology 2025

KISM 2025 BUSAN

Re:Innovation of Semiconductor Manufacturing for AI Ecosystem

[ThD1] Process & Mask

Session Date November 13 (Thu.), 2025

Session Time 09:00-10:50

Session Room D (Sidney Room, 2F)

[ThD1-1] [Plenary] 09:00-09:45

Advances in Lithography and Patterning for Logic and DRAM

Kurt Ronse (imec, Belgium)

[ThD1-2] [Invited] 09:45-10:15

EUV ECO Equal Maximizing Productivity

Heeyoul Lim (SK hynix Inc., Korea)

[ThD1-3] [Invited] 10:15-10:35

Recent Progress in Tin-Based Inorganic Molecular Resists for EUV Lithography and Proposal of Cyclic Siloxane Resist for Blue-X Lithography

Hyun-Dam Jeong (Chonnam Nat'l Univ., Korea)

[ThD1-4] [Invited] 10:35-10:50

Cartridge-Based Van Der Waals Printing for Versatile Device Integration

Dong Hyup Kim (Chonnam Nat'l Univ., Korea)